

GETTERING FILTER AND ASSOCIATED METHOD FOR  
REMOVING OXYGEN FROM A GAS

ABSTRACT OF THE DISCLOSURE

A method and apparatus are provided for removing oxygen and moisture from a gas such that wafers subsequently exposed to the gas develop less haze. The apparatus includes a process chamber for receiving a wafer. The apparatus also includes a gettering filter in fluid communication with the process chamber for removing oxygen from a gas that passes through the gettering filter in route to the process chamber. The gettering filter includes a vessel and a plurality of pieces of an oxidizable material disposed within the vessel. The oxidizable material is selected to oxidize upon exposure to oxygen in the gas such that the gas exiting the vessel has less oxygen than the gas entering the vessel. The oxidizable material may also be selected such that the resulting oxide layer is etchable upon exposure to an etchant, thereby permitting the gettering filter to be regenerated.

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